



US00D849999S

(12) **United States Design Patent** (10) **Patent No.:** **US D849,999 S**
Bae (45) **Date of Patent:** **** May 28, 2019**

(54) **COSMETIC MASK**
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(72) Inventor: **Sangil Bae**, Seoul (KR)
(**) Term: **15 Years**

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(21) Appl. No.: **29/636,995**
(22) Filed: **Feb. 13, 2018**

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(30) **Foreign Application Priority Data**

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Jul. 5, 2017 (KR) 30-2017-0030820
(51) **LOC (11) Cl.** **28-02**
(52) **U.S. Cl.**
USPC **D28/7**
(58) **Field of Classification Search**
USPC D28/4, 7, 9, 99; D29/108–110, 112
CPC A41D 13/00; A41D 13/11; A41D 13/1107;
A41D 13/1161; A41D 13/1169; A41D
13/1192; A41D 13/1184
See application file for complete search history.

(57) **CLAIM**

The ornamental design for a cosmetic mask, as shown and described.

(56) **References Cited**

DESCRIPTION

FIG. 1 is a perspective view of a cosmetic mask showing my new design;
FIG. 2 is a front plan view thereof;
FIG. 3 is a rear plan view thereof;
FIG. 4 is a left side plan view thereof;
FIG. 5 is a right side plan view thereof;
FIG. 6 is a top plan view thereof; and,
FIG. 7 is a bottom plan view thereof.
The broken line showing of environment is for illustrative purposes only and forms no part of the claimed design.

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1 Claim, 5 Drawing Sheets

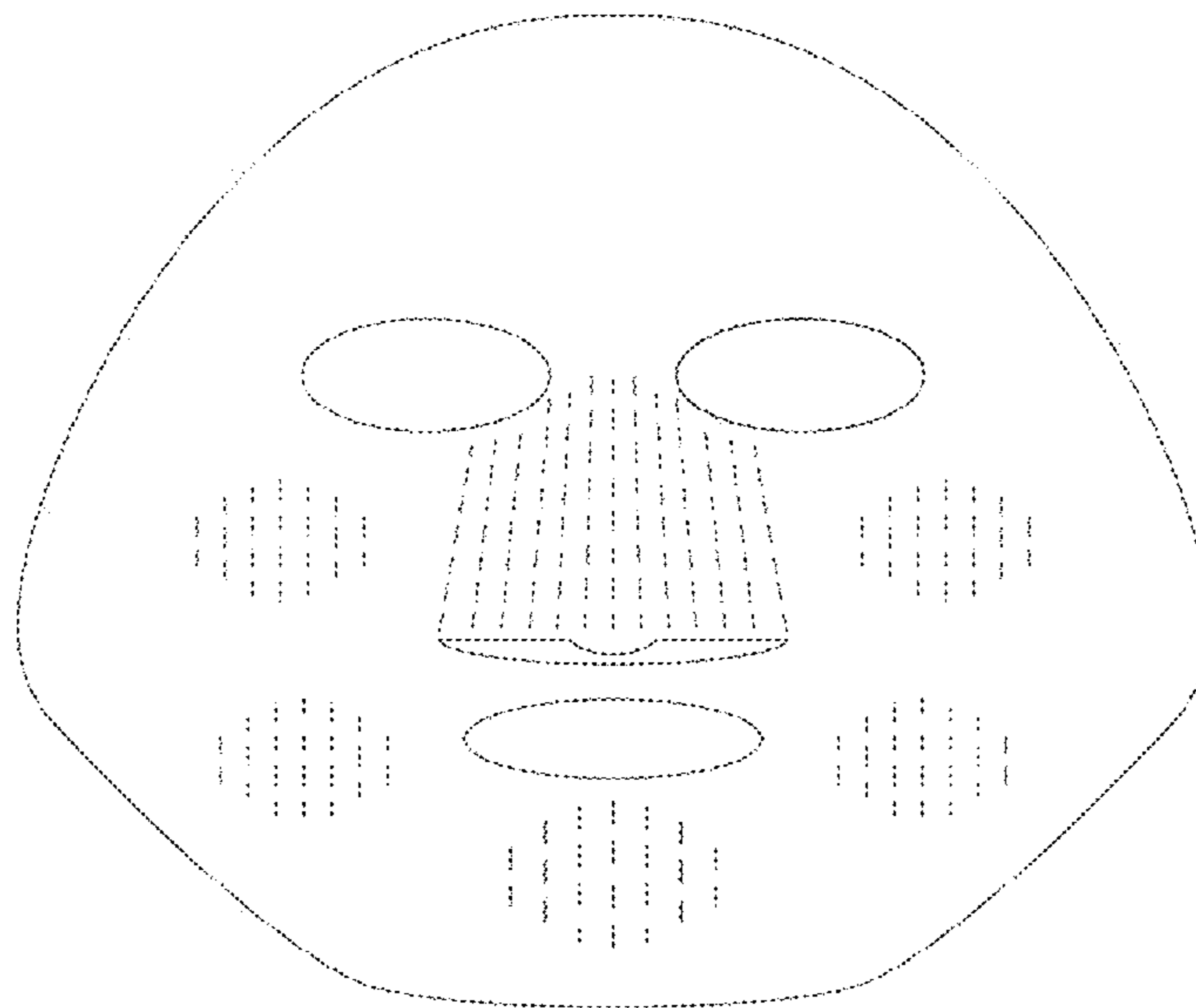


Fig. 1

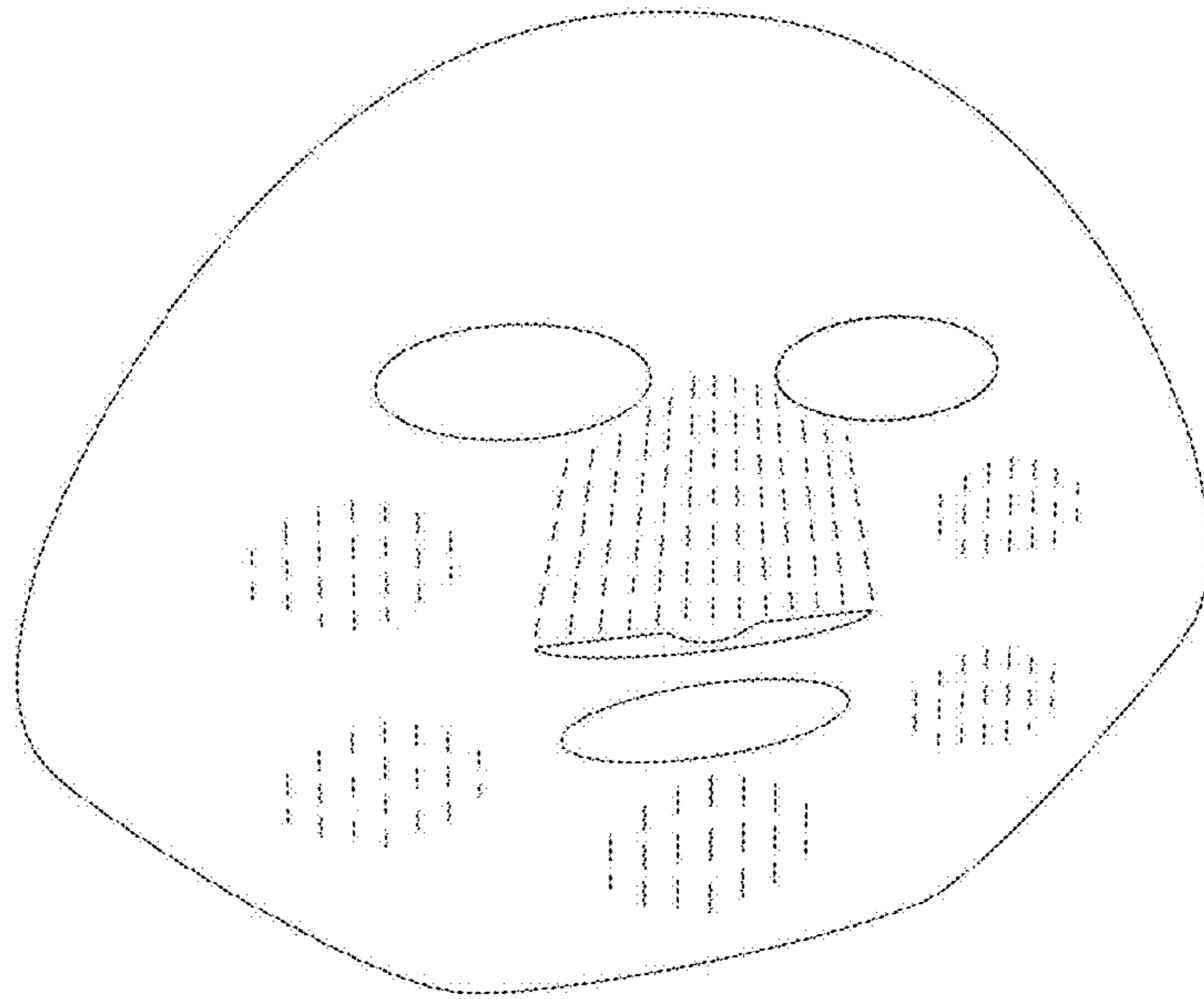


Fig. 2

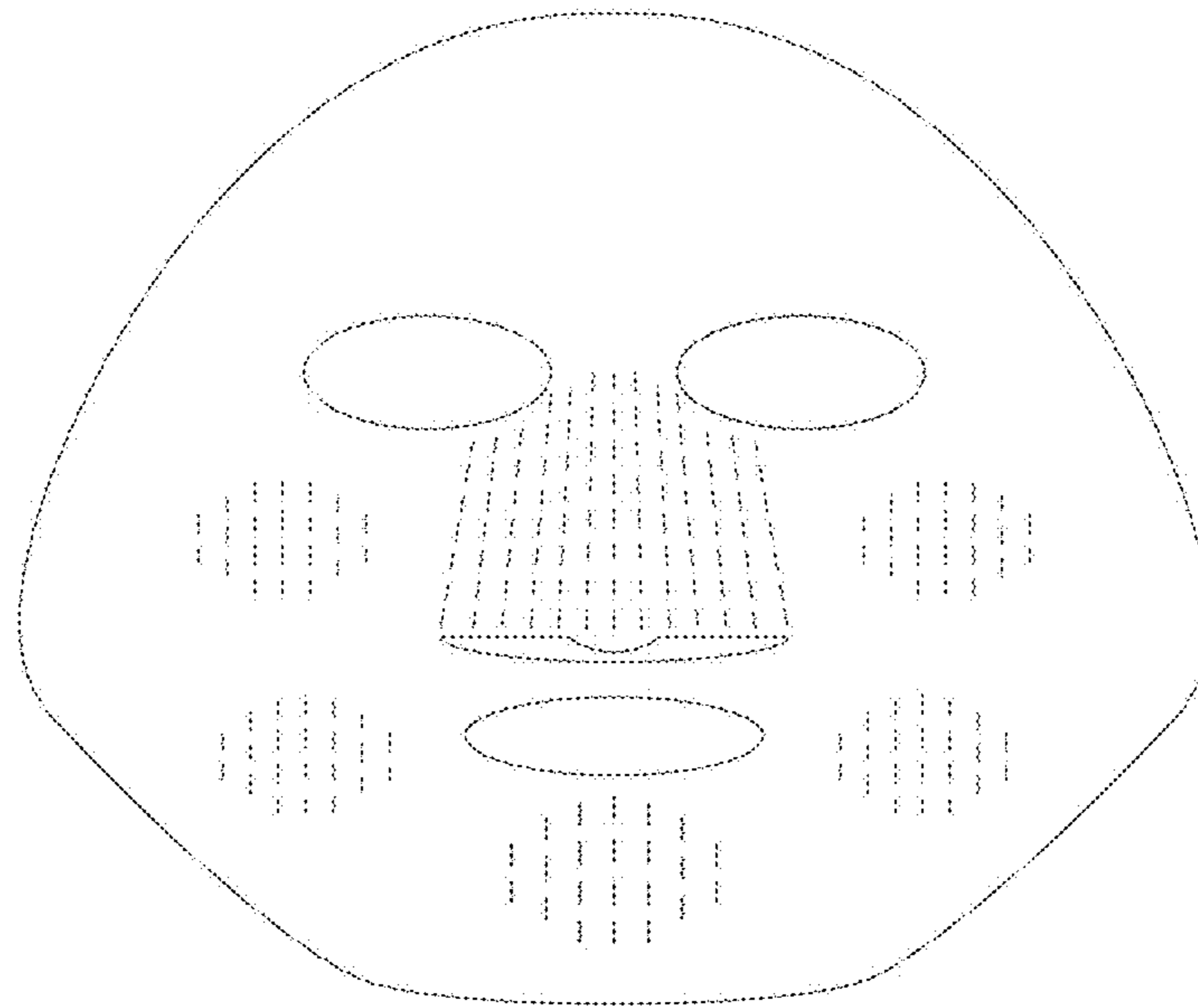


Fig. 3

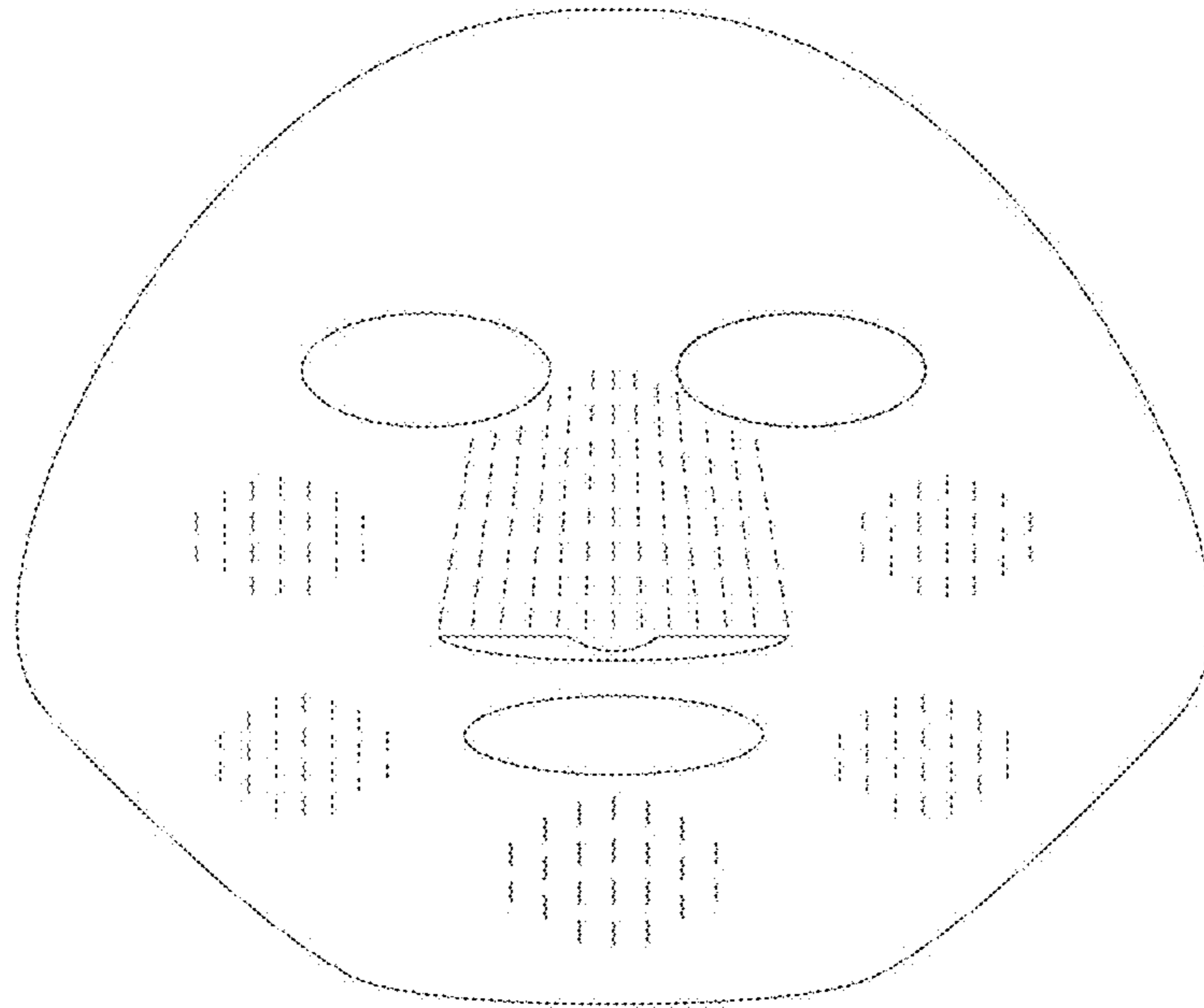


Fig. 4



Fig. 5

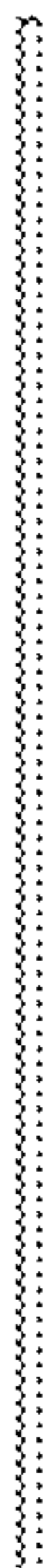


Fig. 6

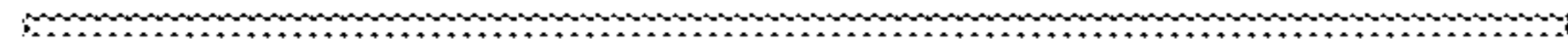


Fig. 7

